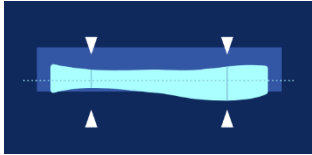


Contactless Wafer Measurement with Capacitive Distance Sensor

Geometrical



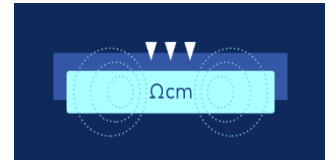
Thickness

TTV (Total Thickness Variation)

Bow, Warp/SORI

Film Stress

Electrical



Resistivity

Sheet Resistance

P/N Dotation Type

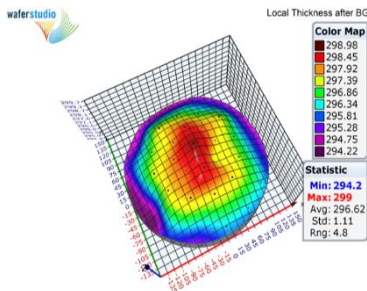
Manual Systems – MX10 Series

Thickness

Flatness / TTV



A pair of capacitive sensors samples four radial profiles (45 degrees) on every. Higher measuring coverage and be increased with number of sensors.



Models	MX102-6	MX102-8	MX1012	MX1018
Wafer Diameter	4", 5", 6"	6", 8"	8" 12"	12", 18"
Accuracy	±0.1 um	±0.1 um	±0.1 um	±0.3 um
Resolution	10 nm	10 nm	10 nm	10 nm
Spartial Resolution	1 mm	1 mm	1 mm	1 mm
Scans	4	4	up to 8	up to 8
Dynamic Range	100 or 350 um	100 or 350 um	100 or 350 um	100 or 350 um
Software	MXNT	MXNT	MXNT	MXNT

Manual Systems – MX20 Series

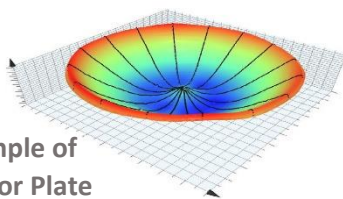
Thickness

Flatness / TTV

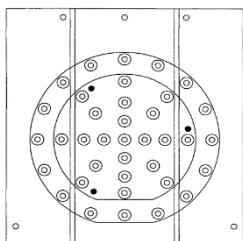
Bow

Warp

Film Stress (Optional)



Example of Sensor Plate Capacitor Points



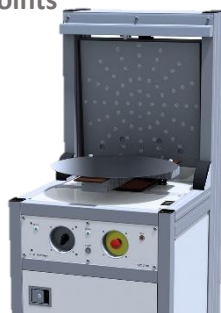
Measures wafer with Sensor Plates that consist of 21, 33, 37, 69 or 73 capacitor points within time range of 5s to 50s for wafer diameters 2" up to 12" or 18".

Customizable to cater for Framed wafer, Taiko wafer, Solar wafer, Non-Conductive and Semi-Insulating wafers



MX203

Manual Loading Series



MX2018-W

Measures 18" Wafer



MX2012-H

Measures 8" or 12" Wafer (Semi-Auto Loading)



MX2012 Measure Wafer in Upright Position to Minimize Gravity-Induced Sag

Contactless Wafer Measurement with Capacitive Distance Sensor

Manual Systems – MX30Series Thickness

Robust and stable instrument for quick and simple manual thickness gauge. Made for a large variety of silicon and solar wafers and pieces of semiconducting or metallic materials. Fully self-calibrating without the need for gauge blocks nor reference wafers. With integrated 5-digit display. Can be connected to PC for Data Collection.

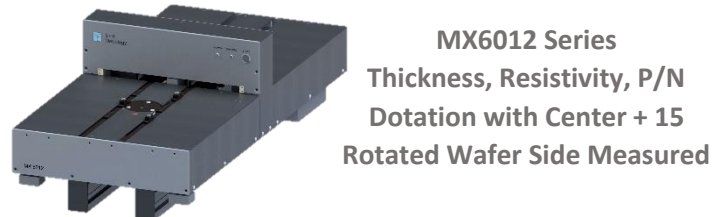
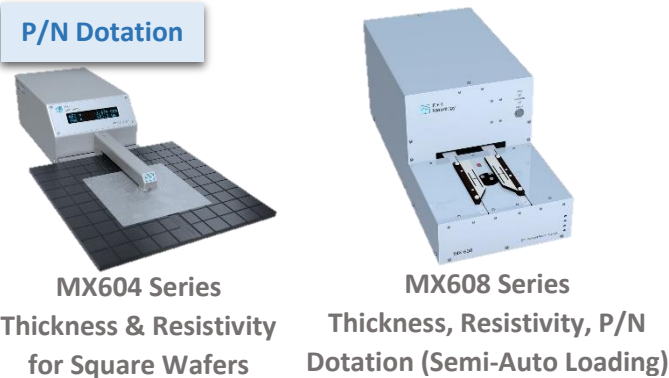


Manual Systems – MX60 Series

Thickness Resistance Sheet Resistance

P/N Dotation

Capable of combining contactless thickness, resistivity and P/N dotation sensors depending on user request. Gauges sheet resistance of semiconducting wafers and conductive films on high-ohm substrates with eddy current method. Surface Photovoltage (SPV) technology for Dotation (P/N). Fully self-calibrating, thus temperature and humidity changes are negligible.

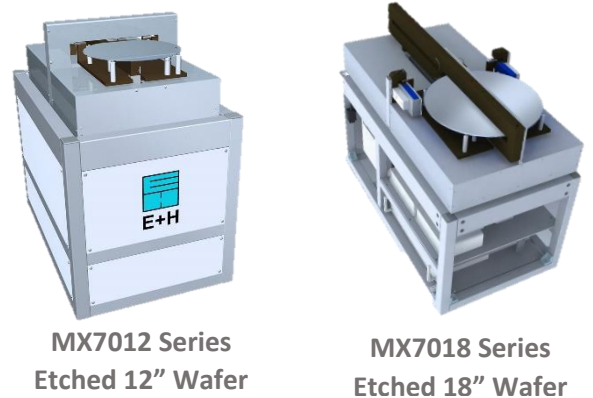


Manual Systems – MX70 Series

Thickness Waviness Roughness

Nanotopography

Capacitive sensors scan a diagonal cut through the center of the wafer (Ingot). On the sides where the saw wire enters and exits, thickness and roughness are measured simultaneously. (The latter with an opto-electronic measuring system.)



Automated Measurement Integration Options:

Belt Sorters Robot Arm Sorters
SECS/GEM Wafer ID Reader



Ex: Belt Sorters & Robot Sorters Integrated with MX20 & 60 Series